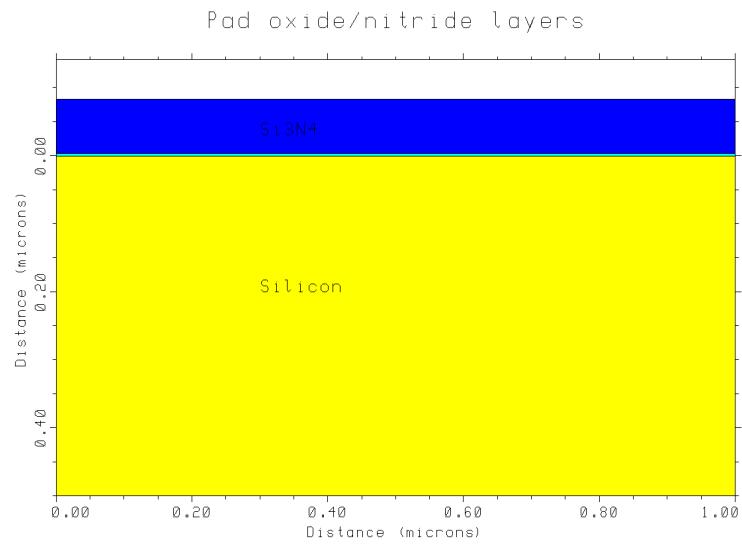


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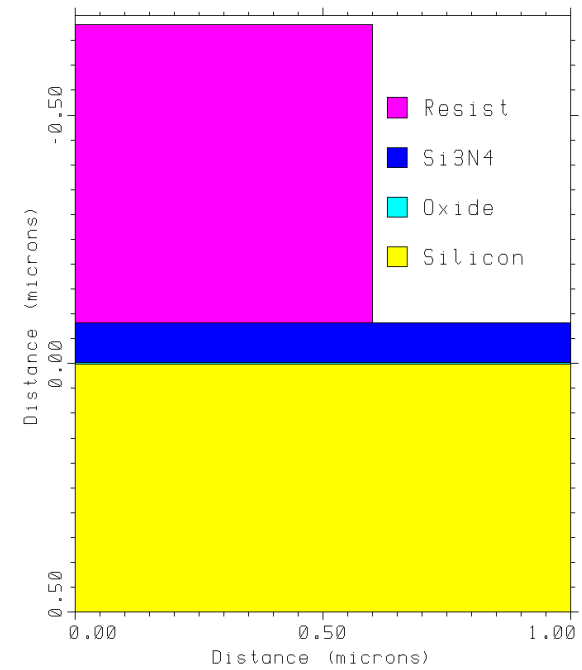
R.W.Mann

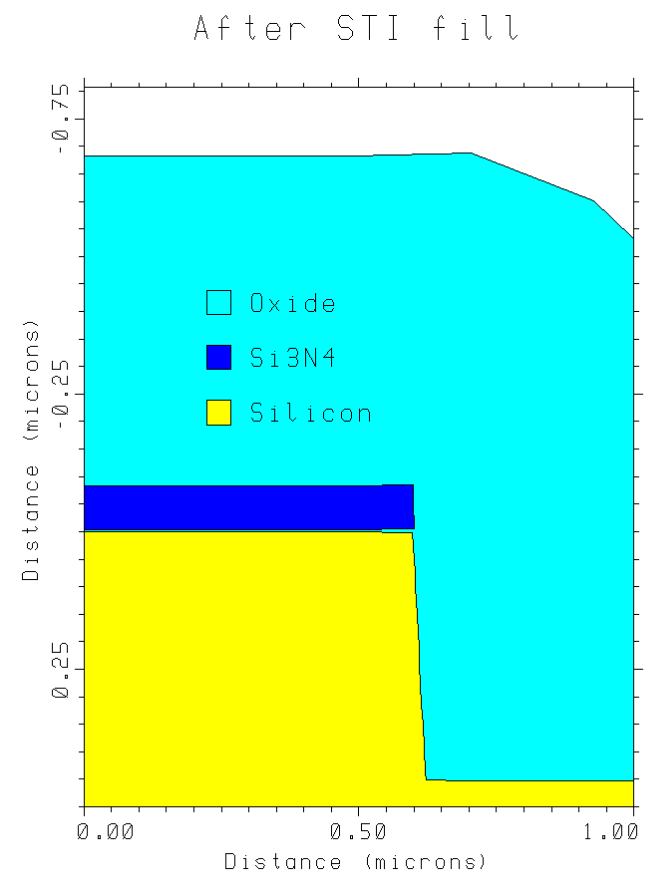
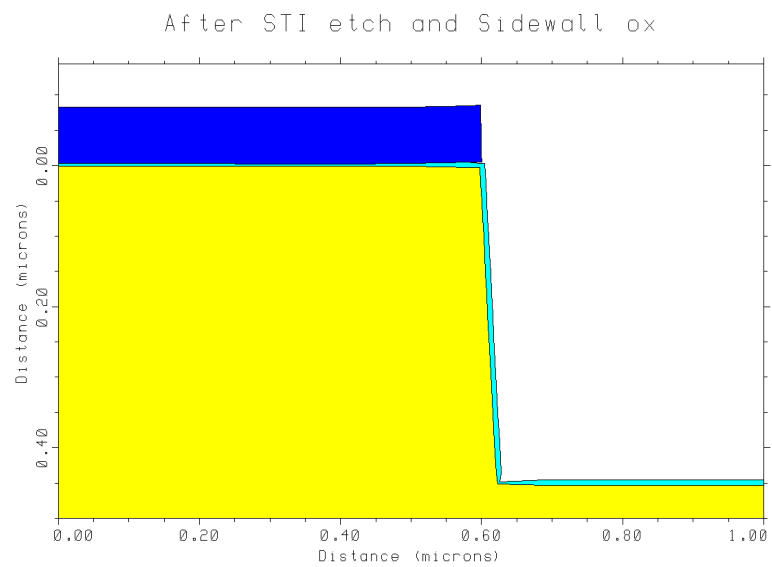
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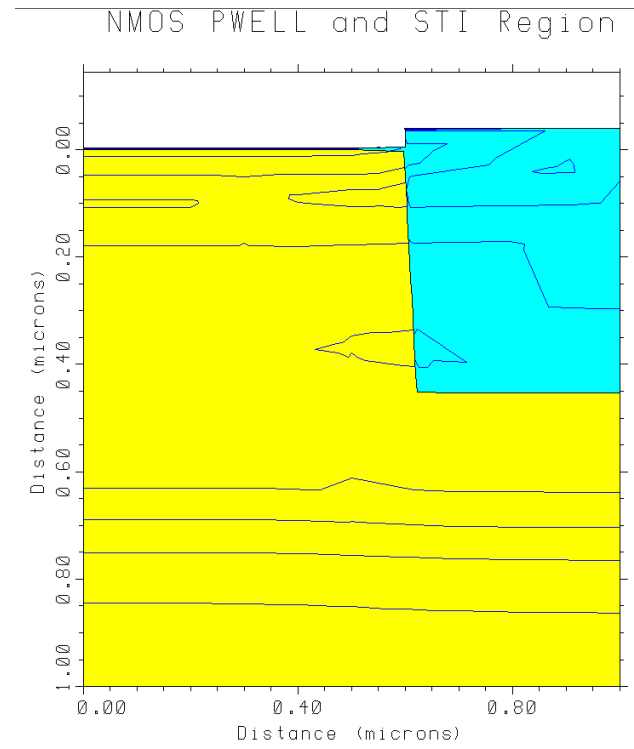
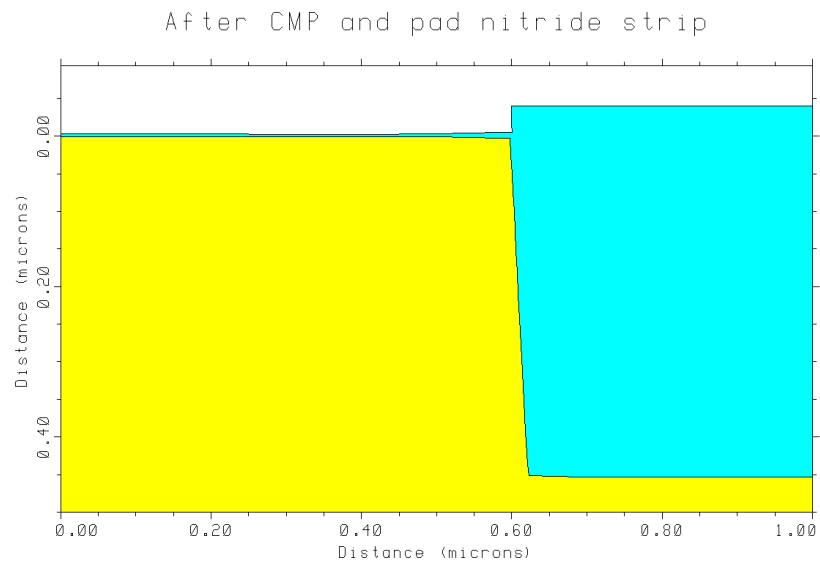
- **65nm technology nmos process flow complete**
 - Pad films through 1st level metal complete in Tsuprem4
 - Well, S/D and channel profiles are extracted
 - S4_nmos65.inp
 - Maskfile.tl1



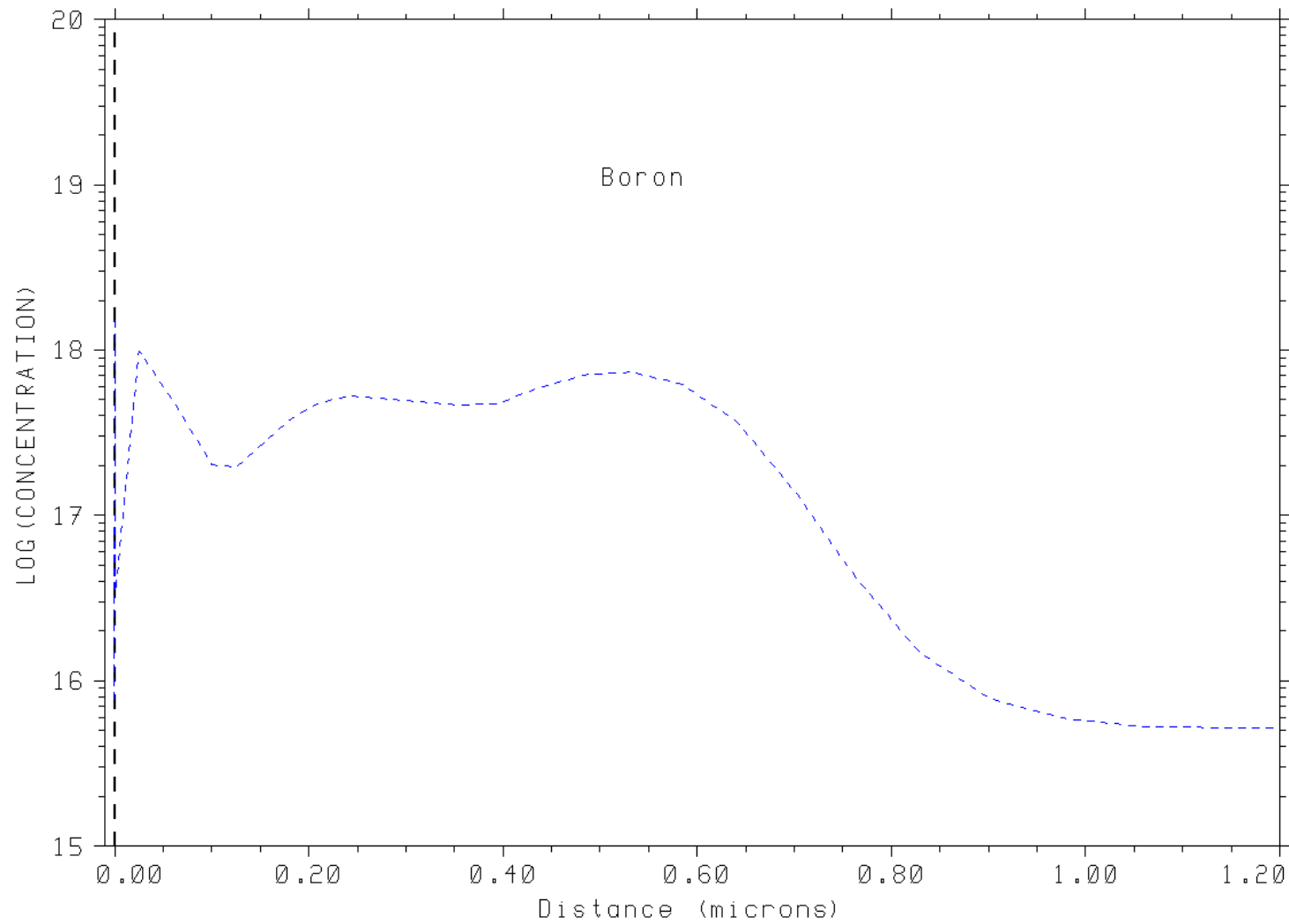
Lithographic step -STI pattern

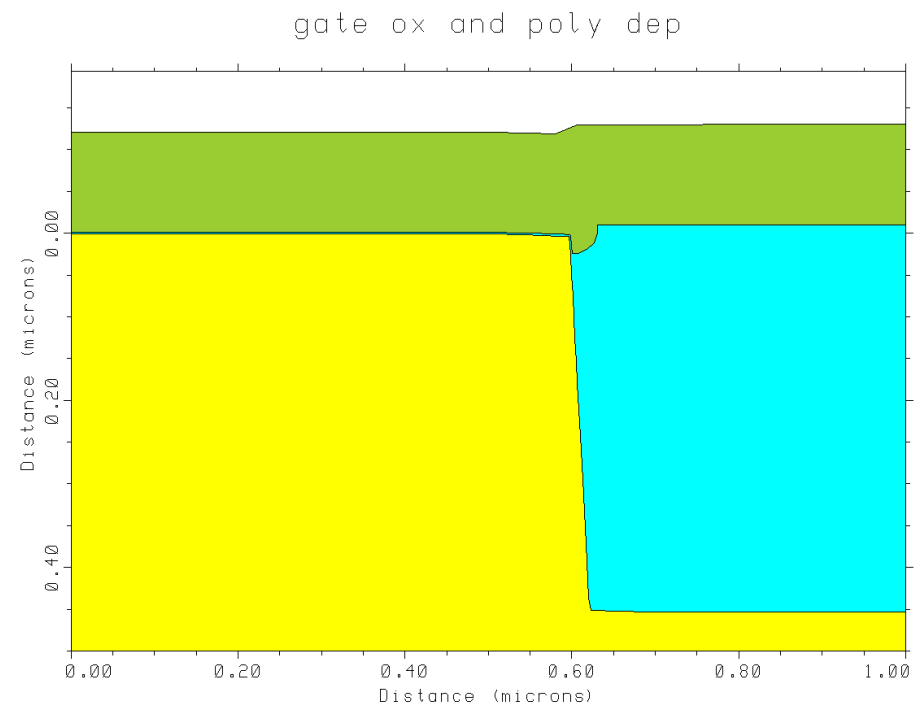




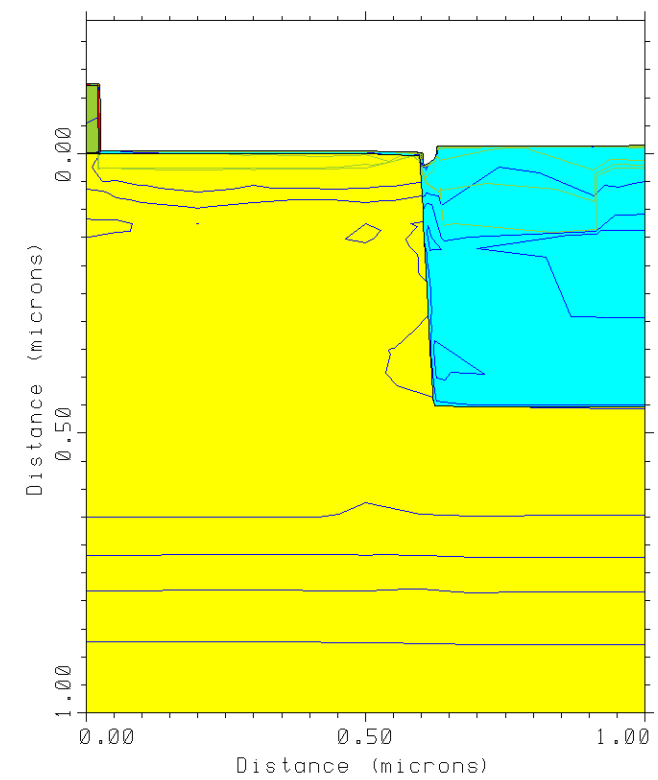


NANO-SCALE CMOS PWELL

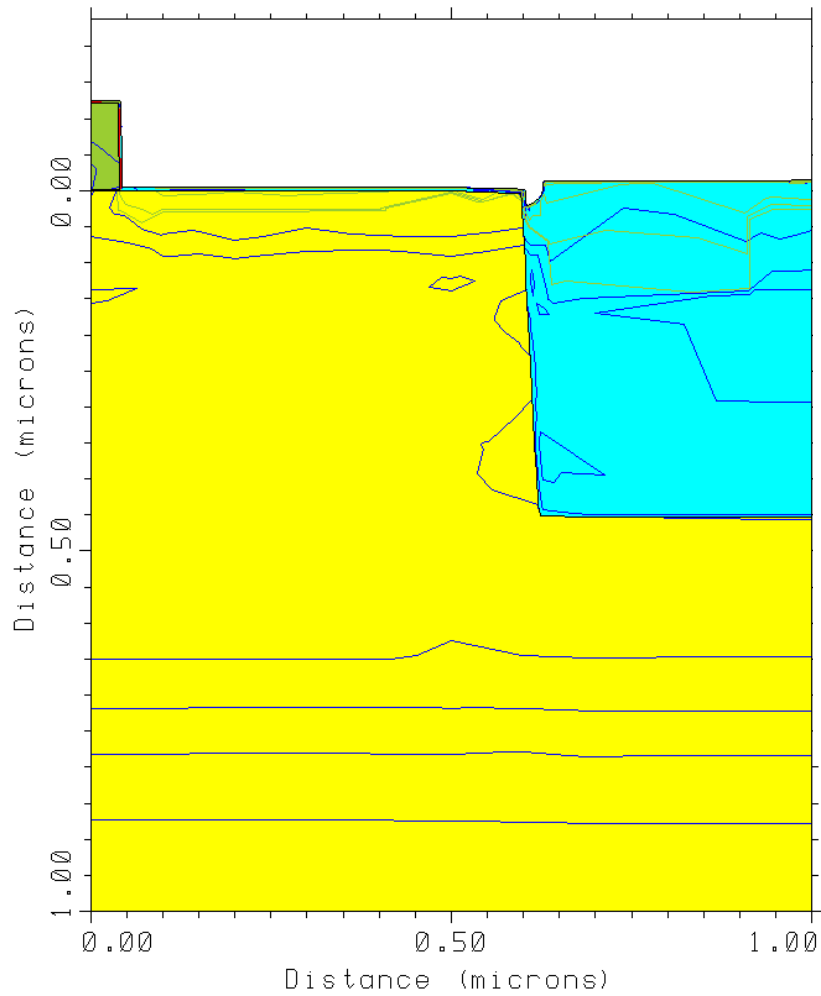




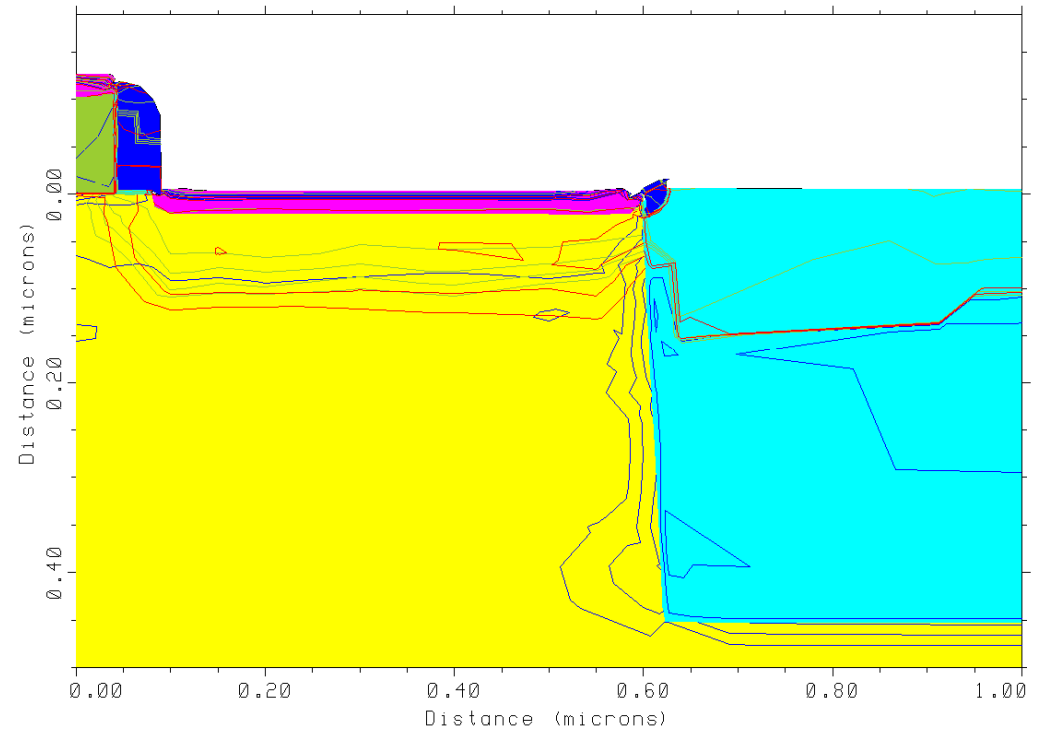
After n+EXT&HALO Implant



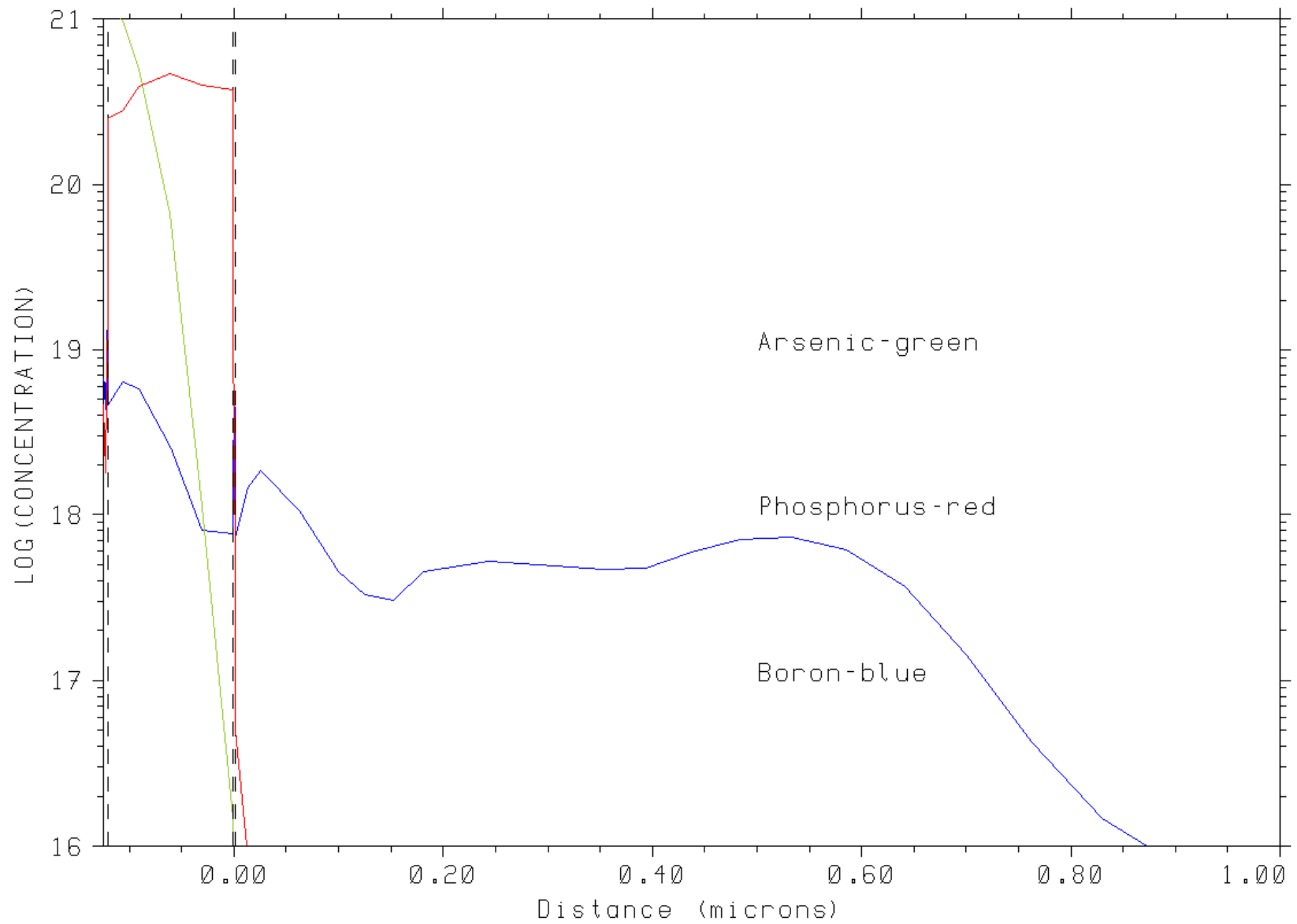
After n+EXT&HALO Implant



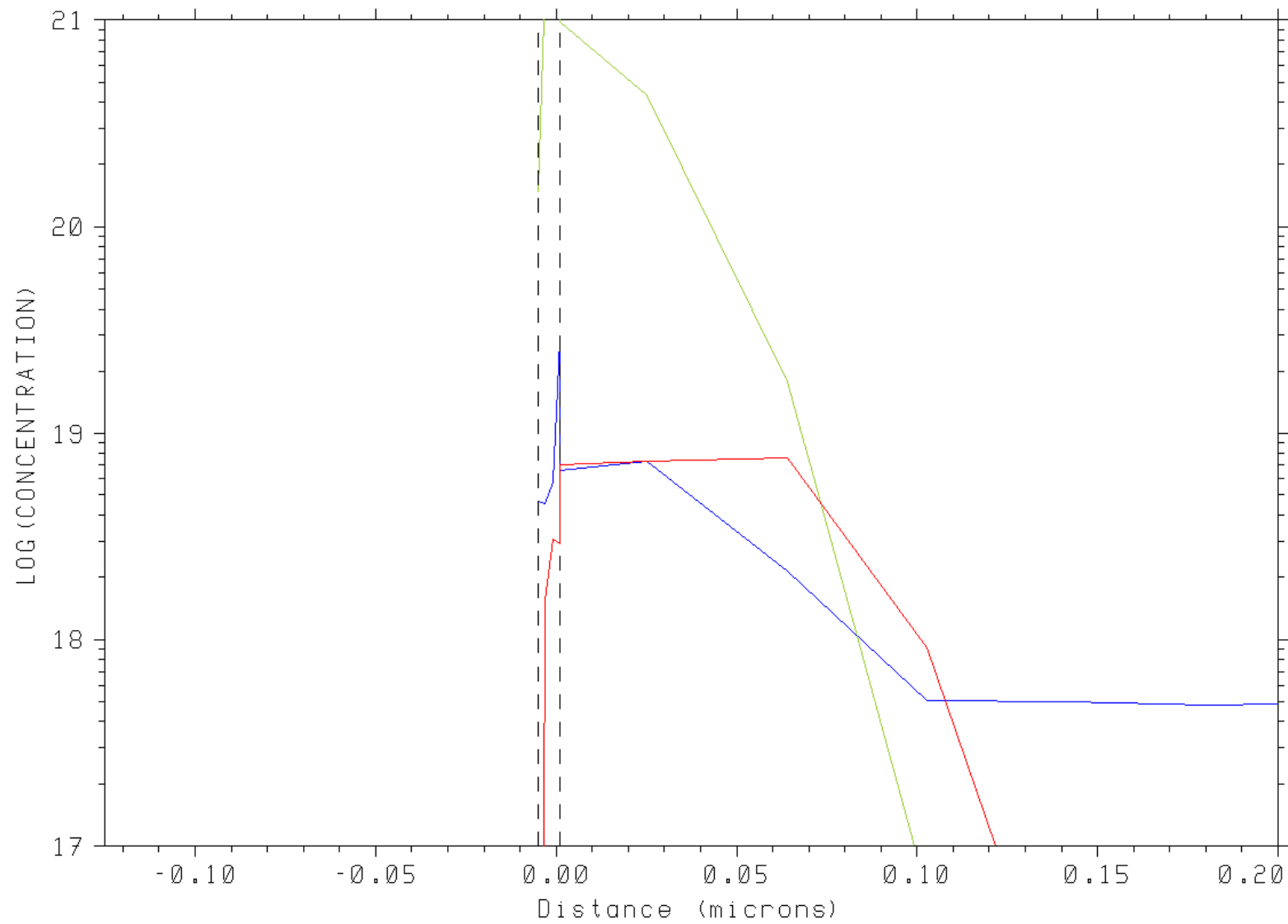
SILICIDED NMOS Structure



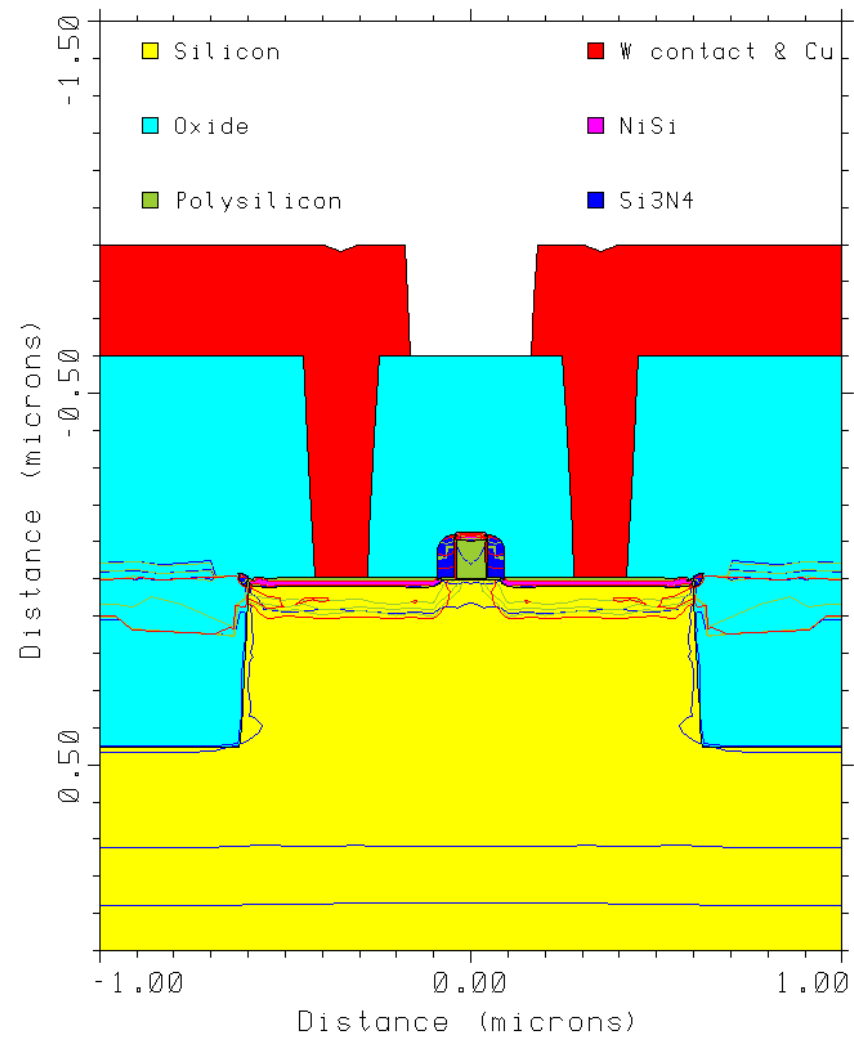
NANO-SCALE CMOS channel



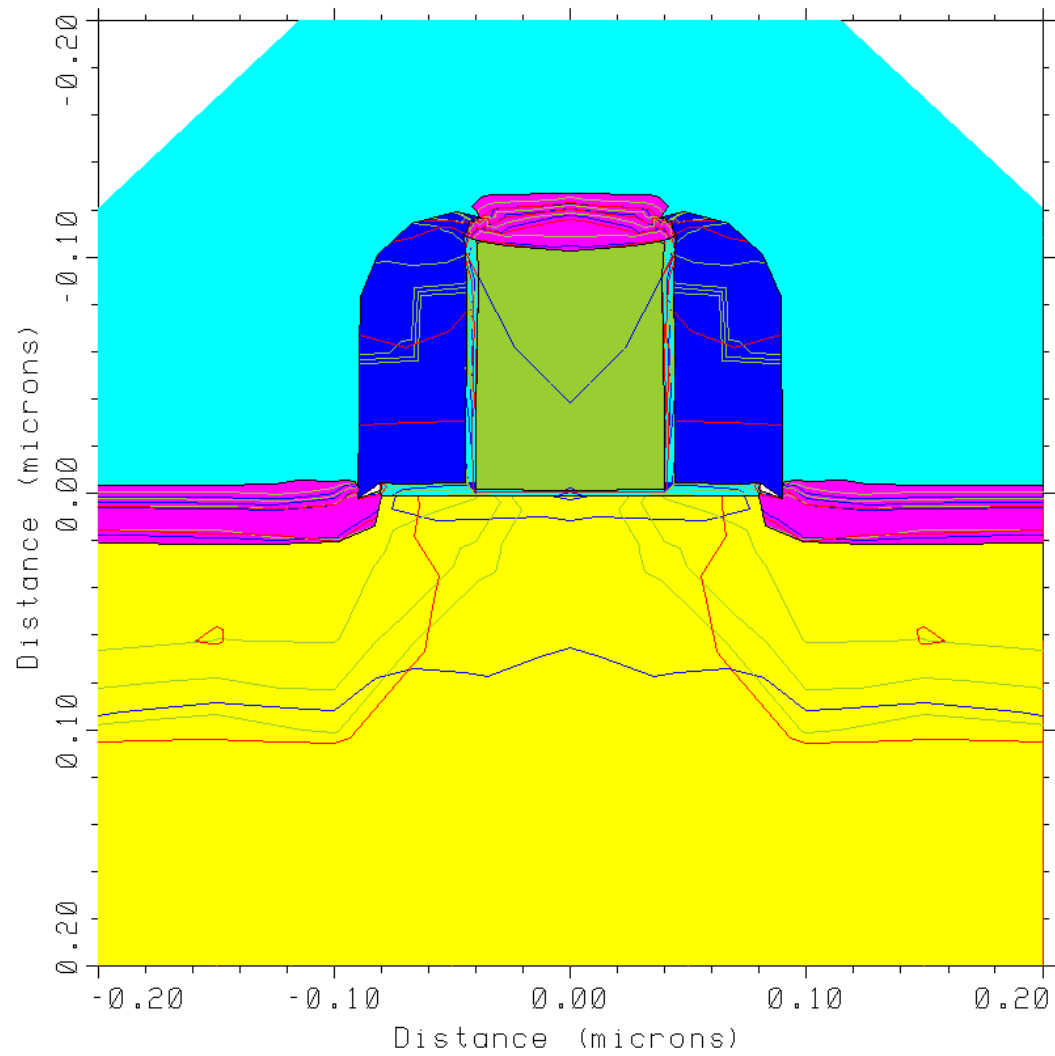
NANO-SCALE NMOS SD



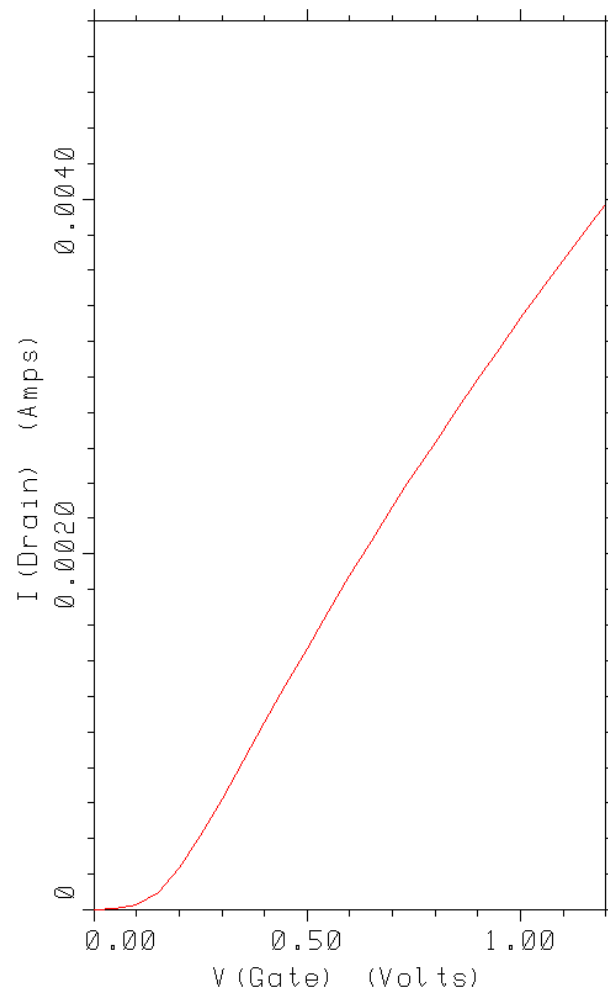
Complete NMOS Structure



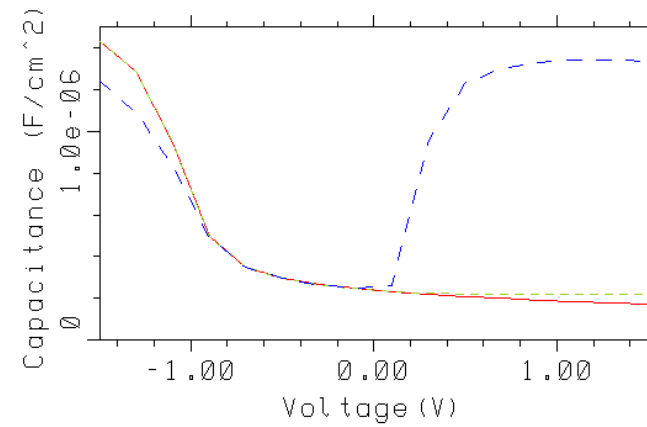
65nm NMOS Device Structure



V_{gs} vs. I_{ds} at V_{ds}=1.2V



MOS C-V



S/D Junction C

